

Title (en)

A method for treating gas containing organohalogen compounds, and catalyst for decomposing the organohalogen compounds

Title (de)

Verfahren zur Behandlung von Gasen die Organohalogenzusammensetzungen enthalten und Katalysator zur Zersetzung von Organohalogenzusammensetzungen

Title (fr)

Procédé pour le traitement de gaz contenant des composants organo-halogènes et catalyseur pour la décomposition des composants organo-halogènes

Publication

EP 0793995 A1 19970910 (EN)

Application

EP 97301219 A 19970225

Priority

- JP 4713096 A 19960305
- JP 917597 A 19970122

Abstract (en)

A method for treating a gas flow containing organohalogen compounds comprising the steps of contacting the gas flow with catalyst at a temperature below 500 DEG C in the presence of an effective amount of steam, wherein the catalyst contains titania, tungsten oxide, and silica, an atomic ratio of Ti and w is in the range of 20 SIMILAR 95 mol % Ti and 80 SIMILAR 5 mol % W, and the amount of silica to titania is in the range of 0.5 SIMILAR 15 wt. %. In accordance with the present invention, the organohalogen compound can be decomposed effectively to carbon monoxide, carbon dioxide, and hydrogen halide. The catalyst of the present invention also has s superior durability.

IPC 1-7

B01D 53/86; **B01J 23/30**

IPC 8 full level

B01D 53/86 (2006.01); **B01J 23/30** (2006.01)

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Citation (search report)

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DE FR NL

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